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Applied Materials' Enabler Etch System Named Best Product by Semiconductor International Magazine

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SANTA CLARA, Calif.--(BUSINESS WIRE)--July 7, 2005--Applied Materials, Inc. today announced that its breakthrough Applied Centura(R) Enabler(R) Etch system is a recipient of Semiconductor International (SI) magazine's 2005 Editors' Choice Best Product Award. The Enabler etch system is engineered for the complex and demanding requirements of copper/low k interconnects. Providing a simplified dual damascene process flow, the system combines multiple sequential etch and ashing steps in a single chamber to reduce cycle time and operating costs.

"Continued advances in semiconductor technology have reshaped the world, and our Editor's Choice Product Awards program honors those products that have made those advances possible," said Pete Singer, Editor-in-Chief of Semiconductor International. "These products embody the very best of innovations on which chip makers rely to make their products smaller, faster, cheaper and more reliable. We congratulate the people and the companies that have had the insight and fortitude to bring these innovative products to the market."

"We are delighted and gratified that our customers have supported the Enabler Etch system for SI's Best Product award," said Dr. Ashok K. Sinha, senior vice president and general manager of Applied Materials' Etch Products Business group. "Advanced logic and memory chips already have over one billion contacts and vias; achieving their flawless operation requires an ultra-high precision dielectric etch process. The Enabler system's unique new capabilities are helping a broad spectrum of customers make their 65nm designs a production reality."

Introduced in 2003, the Applied Centura Enabler Etch system features a novel high-frequency source and decoupled plasma design to provide broad tunability for etching the entire range of dielectric films used in the interconnect, including low k and FSG films. The system has been adopted by leading chipmakers in all major chipmaking regions for use in 90nm logic and memory devices as well as 65nm and 45nm device development.

Applied Materials has won four SI Best Product Awards for its etch systems, most recently in 2002, when the Dielectric Etch eMax Centura(R) was selected. Applied has won a total of 16 Best Product Awards since the award program began in 1989.

Applied Materials (Nasdaq:AMAT), headquartered in Santa Clara, California, is the largest supplier of equipment and services to the global semiconductor industry. Applied Materials' web site is www.appliedmaterials.com.

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